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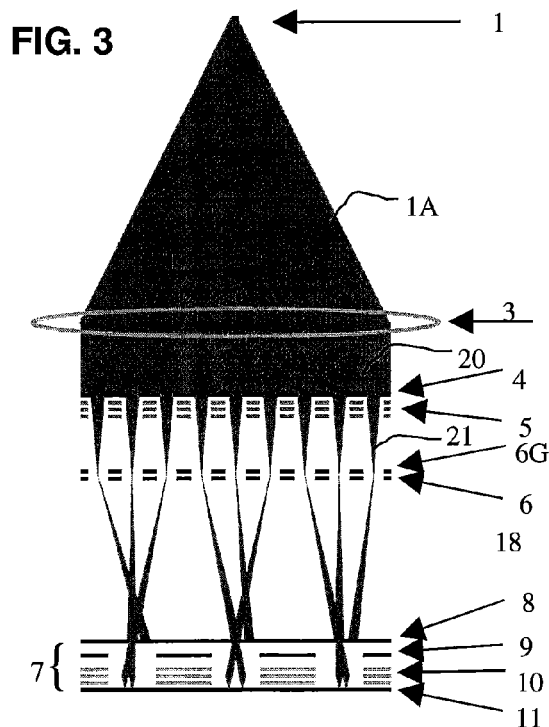
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(54) Title: PROJECTION LENS ARRANGEMENT



(57) Abstract: The invention relates to a charged particle multi-beamlet system for exposing a target (11) using a plurality of beamlets (21). The system has a charged particle source (1), an aperture array (4), a beamlet manipulator, a beamlet blanker (6), and an array of projection lens systems. The charged particle source (1) is configured to generate a charged particle beam (20). The aperture array (4) is configured to define separate beamlets (21) from the generated beam. The beamlet manipulator is configured to converge groups of the beamlets towards a common point of convergence for each group. The beamlet blanker (6) is configured to controllably blank beamlets in the groups of beamlets. Finally, the array of projection lens systems (10) is configured to project unblanked beamlets of the groups of beamlets on to the surface of the target (11). The beamlet manipulator is further adapted to converge each of the groups of beamlets towards a point corresponding to one of the projection lens systems.

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